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APPLICATION NO		FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/856,358		05/22/2001	Takehiko Kezuka	P07223US00/L	6873	
881	7590	10/18/2004		EXAMINER		
		SON PLLC	UMEZ ERONINI, LYNETTE T			
SUITE 900		FAX STREET	ART UNIT	PAPER NUMBER		
ALEXANI	DRIA, VA	A 22314	1765			
				DATE MAILED: 10/18/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Applicat	ion No.	Applicant(s)					
		09/856,3	358	KEZUKA ET AL.					
	Office Action Summary	Examine	ır	Art Unit					
		•	T. Umez-Eronini	1765					
 Period for	The MAILING DATE of this communic	ation appears on th	e cover sheet with the d	correspondence add	ress				
A SHO THE M Extensi after St If the pe - If NO - Failure Any rep	RTENED STATUTORY PERIOD FO AILING DATE OF THIS COMMUNIC ons of time may be available under the provisions of X (6) MONTHS from the mailing date of this communication for reply specified above is less than thirty (30) eriod for reply is specified above, the maximum statuto reply within the set or extended period for reply willy received by the Office later than three months after patent term adjustment. See 37 CFR 1.704(b).	CATION. Tay CFR 1.136(a). In no endication. days, a reply within the statory period will apply and will by statute.	vent, however, may a reply be tir stutory minimum of thirty (30) day will expire SIX (6) MONTHS from plication to become ABANDONE	mely filed /s will be considered timely. the mailing date of this con TO (35 U.S.C. 8 133)	nmunication.				
Status					•				
1)⊠ R	lesponsive to communication(s) filed	on 30 July 2004							
		o) This action is	non-final.						
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Dispositio	n of Claims								
4a 5)□ C 6)□ C 7)⊠ C	Claim(s) 1,2 and 5-16 is/are pending is a) Of the above claim(s) is/are claim(s) is/are allowed. Claim(s) 1, 2, 5, 6, and 9-16 is/are rejudiam(s) 7 and 8 is/are objected to. Claim(s) are subject to restriction	e withdrawn from co							
Applicatio	n Papers								
10)□ Th A R	ne specification is objected to by the ne drawing(s) filed on is/are: a pplicant may not request that any objective placement drawing sheet(s) including the oath or declaration is objected to the	a) accepted or by on to the drawing(s) ne correction is requi	be held in abeyance. See red if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFF					
Priority un	der 35 U.S.C. § 119								
12)⊠ Ac a)⊠ 1. 2. 3.	knowledgment is made of a claim fo	ocuments have been been been the priority documents all Bureau (PCT Rules)	en received. en received in Applicati ents have been receive le 17.2(a)).	on No ed in this National S	tage				
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Attachment(s)	f References Cited (PTO-892)		4) Interview Summary	(PTO 413)	,				
2)	f Draftsperson's Patent Drawing Review (PTC ion Disclosure Statement(s) (PTO-1449 or PTo(s)/Mail Date	0-948) [*] O/SB/08)	Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:	nte	52)				

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 2. Claims 1, 11, 12, 15, and 16 are rejected under 35 U.S.C. 102(b) as being anticipated by Schwabe (US 3,977,925).

Schwabe teaches, ". . . an etchant composed of a mixture containing for each 100 gr of HNO₃ (same as applicants' inorganic acid), 20 gr of H₂O, 4 gr of HF and 110 gr of CH₃COOH (Abstract), which reads on and encompasses,

An etching solution comprising:

- (i) hydrofluoric acid;
- (ii) water in a concentration of 30% by weight or lower; and
- (iii) at least one member selected from the group consisting of an organic acid, an inorganic acid and an organic solvent having a hetero atom, whose content ranges from 30 to 99.9% by weight. Since Schwabe teaches the same etchant as claimed by applicants, then using Schwabe's etchant in the same manner as the claimed invention would inherently result wherein the etching solution has a ratio of an etch rate of a boron silicate glass film (BSG) or boron phosphosilicate glass/ an etch rate of a thermal oxide film (THOX) at 25°C of 20 or higher, in claim 1.

Art Unit: 1765

The said above reads,

wherein the solution comprises an inorganic acid, in claim 11;

wherein the inorganic acid has a pK_a value at 25°C of 2 or lower, in claim 12;

Schwabe further teaches a process for producing a semiconductor arrangement from a monocrystalline silicon substrate for use in an integrated circuit by etching a silicon substrate (claim 1), which reads on,

a method for producing an etched article by etching an article to be etched with the etching, in claim 15; and

an etched article which is obtainable by the method of claim 15, as in claim 16.

Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to

Art Unit: 1765

consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

5. Claims 5, 9, and 10 are rejected under 35 U.S.C. 103(a) as obvious over Schwabe (US '925), as applied to claim 1 above, and in view of McCollister et al. (US 4,273,826).

Schwabe differs in failing to teach in failing to specify the % by weight ratio of the components of the etching solution as recited in claims 5, 9, and 10.

McCollister teaches an etchant solution containing a 47 weight percent solution of HF in water, 7.6 ml of a 37 weight percent of HCl in water and 112 ml of alcohol consisting of 90.2 weight percent ethanol, 4.8 weight percent methanol, and 5 weight percent isopropanol (column 4, lines 40-45) and illustrates that the specific combination of HF, water, and organic solvent (i.e. ethanol, methanol, and isopropanol) and HF, HCl, and water is known. As a result, it would have been obvious to one of ordinary skill in the art at the time the invention was made to select any proportion of HF, alcohol, and water and HF, HCl, and water in the reference of McCollister that would effectively accomplish the disclosed composition because it has been held that there is no invention where the difference in proportions is not critical and was ascertained by routine experimentation because the determination of workable ranges is not considered inventive. See In re Swain and Adams, 70 USPQ 412 (CPA 1946).

Art Unit: 1765

6. Claims 2 and 6 is rejected under 35 U.S.C. 103(a) as being unpatentable over Schwabe US '925) as applied to claim 1 above, and further in view of Grant et al. (US 5,439,553).

Schwabe differs in failing to teach a solvent in the etching solution has a relative dielectric constant of 61 or lower, **in claim 2**.

Grant teaches an etchant comprising HF along with organic materials such as methanol, isopropanol, acetone and acetic acid (column 5, line 63 – column 6, line 6 and claims 3-5) and further teaches these solvents prevent condensation and other contaminants on the oxide surface (column 3, lines 43-54)

It would have been obvious to one skilled in the art at the time of the claimed invention to modify Schwabe by employing a solvent having a dielectric constant of less than 61 as taught by Grant for the purpose of preventing deposition of contaminants of the substrate (Grant, column 3, lines 43-54).

Schwabe differs in failing to teach in failing to specify the % by weight ratio of the components of the etching solution as recited, **in claim 6**.

Grant discloses wet etching has prevalently been disclosed with HF, water and acetic acid alone (column 1, lines 57-59) and illustrates that the specific combination of HF, water, and acetic acid is known. As a result, it would have been obvious to one of ordinary skill in the art at the time the invention was made to select any proportion of HF, acetic acid, and water in the reference of Grant that would effectively accomplish the disclosed composition because it has been held that there is no invention where the

Art Unit: 1765

difference in proportions is not critical and was ascertained by routine experimentation because the determination of workable ranges is not considered inventive. See In re Swain and Adams, 70 USPQ 412 (CPA 1946).

7. Claim 14 is rejected under 35 U.S.C. 103(a) as being unpatentable over Schwabe (US '925) as applied to claim 1 above, and further in view of Wanlass (US 3,997,381).

Schwabe differs in failing to specify the percent weight ratio of HF: HNO3: water is 0.01-50: 1-70: 0-99.

Wanlass teaches an etching solution comprising of hydrofluoric (49% by weight), nitric (70% by weight), (column 7, lines 10-14), which encompasses the percent weight ratio of HF:HNO₃:water is 0.01-50:1-70:0-99 and illustrates that the specific combination of HF, HNO₃, and water is known. As a result, it would have been obvious to one of ordinary skill in the art at the time the invention was made to select any proportion of HF, HNO₃, and water in the reference of Wanlass that would effectively accomplish the disclosed composition because it has been held that there is no invention where the difference in proportions is not critical and was ascertained by routine experimentation because the determination of workable ranges is not considered inventive. See In re Swain and Adams, 70 USPQ 412 (CPA 1946).

Application/Control Number: 09/856,358 Page 7

Art Unit: 1765

Allowable Subject Matter

8. Claims 7 and 8 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

9. The following is a statement of reasons for the indication of allowable subject matter: The prior art of record taken alone or in combination fails to suggest, teach or render obvious an etching solution comprises a constituent ratio respectively, of HF: tetrahydrofuran: water and HF: acetone: water is 0.1-50% by weight: 30-99.9% by weight: 0-70% by weight.

Response to Arguments

10. Applicant's arguments, see Remarks, filed July 30, 2004, with respect to the rejection(s)of claim(s) 1, 11, 15, and 16; and 2-10, 12-13, and 14 under 102(b) and 103(a) respectively have been fully considered and are persuasive. Therefore, the rejection has been withdrawn. However, upon further consideration, a new ground(s) of rejection is made in view of applicants' amendment of claims 1, 5-6, 9-14, which recites "an etching solution comprising: --(i)-- hydrofluoric acid; --(ii) water in a concentration of 30% by weight or lower; and (iii) at least one member selected from the group consisting of an organic acid, an inorganic acid and an organic solvent having a hetero atom, whose content ranges form 30 to 99.9% by weight, -- . . ."

Conclusion

11. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of

Art Unit: 1765

Page 9

the advisory action. In no event, however, will the statutory period for reply expire later

than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Lynette T. Umez-Eronini whose telephone number is

571-272-1470. The examiner is normally unavailable on the First Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Nadine Norton can be reached on 571-272-1465. The fax phone number

for the organization where this application or proceeding is assigned is 703-872-9306.

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Art Unit 1765

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September 6, 2004

NADINE G. NORTON SUPERVISORY PATENT EXAMINER Mad